

Special Issue

Research Progress in Dust Control Technology

Message from the Guest Editors

This Special Issue aims to publish state-of-the-art technologies for dust control across various production and operational settings. The scope covers typical dust sources, including mining, tunnel construction, metal and powder processing, thermal power plants, cement plants, and waste incineration. Research topics encompass the optimization and enhancement of conventional dust control technologies (such as spraying, ventilation, dust collectors, foam suppression, and chemical suppressants), the application of emerging technologies and materials (including nano-coating, electrostatic and pulsed spraying, and bio-based suppression), digitalization and intelligent control (such as the Internet of Things, artificial intelligence, and digital twins), and the development of integrated dust control systems.

Guest Editors

Dr. Jianguo Liu

Prof. Dr. Shihang Li

Dr. Chaohang Xu

Deadline for manuscript submissions

30 May 2026



Processes

an Open Access Journal
by MDPI

Impact Factor 2.8
CiteScore 5.5



mdpi.com/si/255350

Processes
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
processes@mdpi.com

[mdpi.com/journal/
processes](https://mdpi.com/journal/processes)





Processes

an Open Access Journal
by MDPI

Impact Factor 2.8
CiteScore 5.5



[mdpi.com/journal/
processes](https://mdpi.com/journal/processes)



About the Journal

Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

Author Benefits

Open Access:

free for readers, with article processing charges (APC) paid by authors or their institutions.

High Visibility:

indexed within Scopus, SCIE (Web of Science), Ei Compendex, Inspec, AGRIS, and other databases.

Journal Rank:

CiteScore - Q2 (Chemical Engineering (miscellaneous))